

GPI8HIRGIC

GaN Power IC in DFN5x6 Package

Preliminary Datasheet version: 1.0

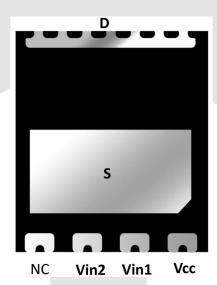
Features

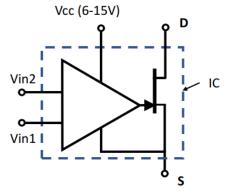
BV _{dss}	R _{dson}	l _{ds}	
650V	175 mΩ	7.5 A	

- Edge-triggered high-side power IC
- Small transformer isolation
- Wide Vcc range
- Low Rds and high dv/dt capability
- Extremely low input/output capacitance
- Fast switching
- Low Profile

Applications

- High-side switch in switching power applications
- Power adapters and power delivery chargers





Description

These devices are power IC based on 650 V Power GaN HEMTs using proprietary (US patent pending) E-mode GaN on silicon technology. The gate driver is integrated with the main power transistor resulting in fast switching, high system power density and low cost. Edge triggering narrow pulse is used to control device turn-on/off. This results in high noise immunity and small and inexpensive transformer for isolation and level shifting for the high-side switch in a half bridge application.



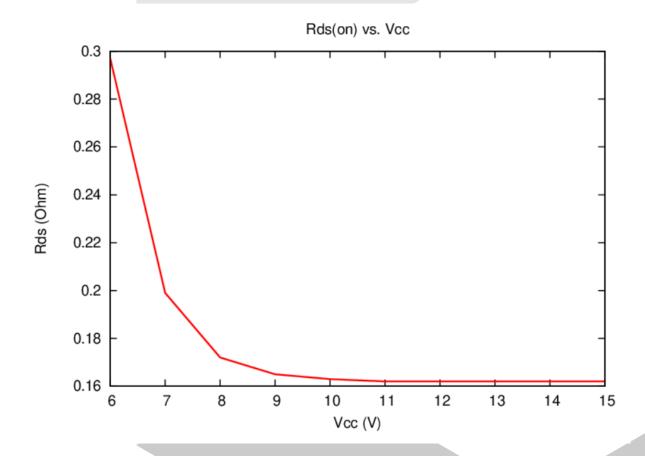
Basic	Parameters			Test data			
	Paramete rs		Conditions	Min	Typical	Max	Unit
1	BV _{dss}	Drain-Source breakdown voltage	V _{gs} =0V I _d =10uA		650		٧
2	R _{dson}	Static drain-source on resistance, $T_C = 25^{\circ}C$	V _{gs} =6V I _d =1.8A	165	175	300	mΩ
3	Vcc	Drive supply voltage		6	10	15	V
4	Vin1	Turn-off narrow pulse triggering pulse	Pulse width 50ns-300ns	2.5	5	8	V
5	lin1	Turn-off current	Pulse width 50ns-300ns		0.02		mA
6	Ciss1	Input capacitance			0.3		pF
7	Qg1	Input gate charge			6.5		fC
8	Vin2	Turn-on narrow pulse triggering pulse	Pulse width 50ns-300ns	2.5	5	8	V
9	lin2	Turn-off current	Pulse width 50ns-300ns		0.02		mA
10	Ciss2	Input capacitance			0.3		pF
11	Qg2	Input gate charge			6.5		fC
Swite	Switching Performance			Test data			
	Paramete rs		Conditions	Min	Typical	Max	Unit
1	t _{d(on)}	Turn-on delay time	V _{ds} =385V		15		ns
2	t _r	Vds rise time (turn-off)	I _d =1.6A		8		ns
3	t _{d(off)}	Turn-off delay time	Vin1/2=5V		10		ns
4	t _f	Vds Fall time (turn-on)	V _{dd} =6.5V		12		ns

Device Characteristics



Electrical Performance

Rds(on) vs. Vdd at Id=15mA

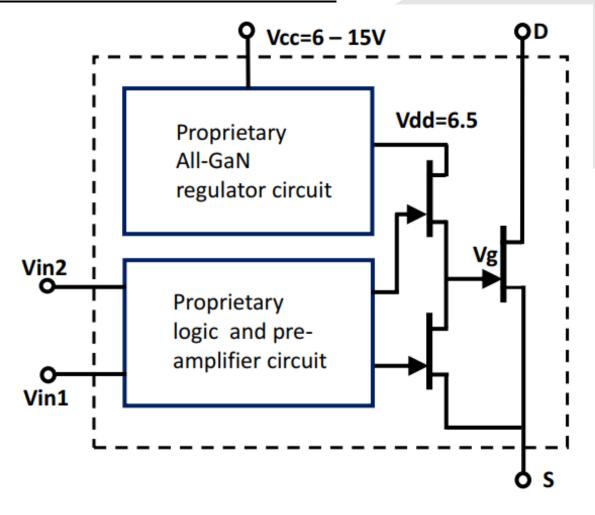


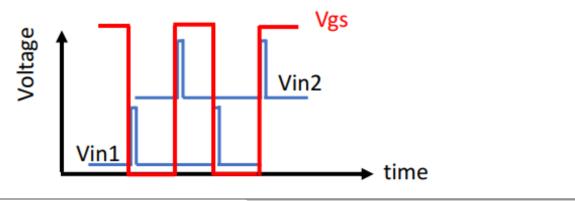


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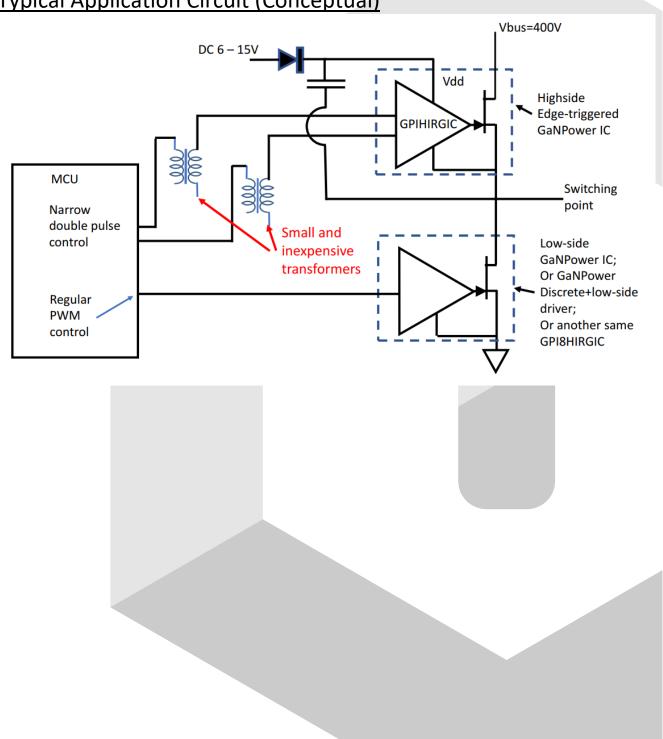
Internal Schematic and waveforms







Typical Application Circuit (Conceptual)



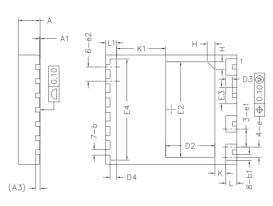


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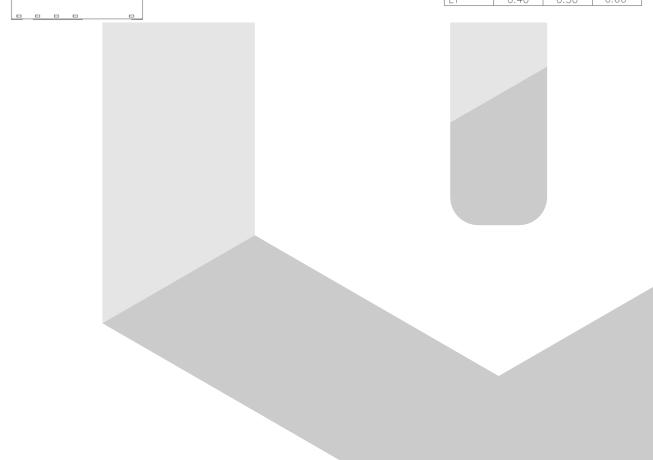
Package Information





COMMON DIMENSIONS
(UNITS OF MEASURE=MILLIMETER)

SYMBOL	MIN	NOM	MAX		
А	0.90	1.00	1.10		
A1	0.00	0.02	0.05		
А3	0.203REF				
b	0.20	0.25	0.30		
b1	0.225	0.275	0.325		
D	5.90	6.00	6.10		
E	4.90	5.00	5.10		
D2	2.15	2.25	2.35		
E2	4.27	4.37	4.47		
D3	0.20	0.30	0.40		
E3	0.65	0.75	0.85		
D4	0.20	0.30	0.40		
E4	4.525	4.625	4.725		
е	0.375	0.475	0.575		
e1	0.725	0.825	0.925		
e2	0.55	0.65	0.75		
Н	0.35REF				
K	0.35	0.50	0.65		
K1	2.10	2.25	2.40		
L	0.40	0.50	0.60		
L1	0.40	0.50	0.60		





GaN HEMT Frequently Asked Questions

1	Q: Can we do pin to pin switch for silicon MOSFET or IGBT?
	A: The short answer is no. GaN HEMT power devices are far superior than the best silicon
	devices such as super junction MOSFETs. However, due to different requirements of gate
	driving voltage and extremely high dv/dt slew rate, special drivers and optimized PCB layouts
	are recommended to minimize the impact from circuit parasitics. Some packaging forms such
	as GaNPower's DFN packaged devices offer both sense and force for the source terminal. Also,
	for traditional TO220 packages, please be advised that the pins are arranged as Gate – Source
	-Drain, and the thermal pad is connected to the source instead of drain.
2	Q: Are GaN power devices reliable?
	A: GaN power HEMTs have been tested by GaNPower and many other vendors, users and
	testing facilities to be as reliable (if not better than) silicon counterparts.
3	Q: How do GaN power devices compare with SiC?
	A: Currently GaN power HEMT devices are most suitable for low to medium voltage (≤1200V)
	and power (<50KW) applications.
4	Q: Do we need to parallel an FRD for applications such as inverters?
	A: GaN devices are different from silicon MOSFET or IGBT in that they have no inherent PN
	junction diodes that cause reverse recovery issue. User do not need to parallel an FRD for the
	purpose of suppressing the body diode reverse recovery effect, since GaN HEMT can operate
	in both first and third quadrants. However, care should be taken for the dead time power loss
	since the Vsd voltage of GaN HEMT is usually close to 2V. This is especially true when a negative
	gate voltage is applied.
5	Q: Can we parallel GaN HEMT devices?
	A: Yes, GaN HEMT is ideal for paralleling, due to positive temperature coefficient of Rdson
	and slightly positive temperature coefficient of threshold voltage.